

A METHOD FOR PRODUCING A HARD MASK IN A CAPACITOR DEVICE
AND A HARD MASK FOR USE IN A CAPACITOR DEVICE

ABSTRACT

A method for producing a hard mask and a hard mask for use in a capacitor device comprises the steps of applying a photosensitive sol-gel layer to the capacitor device, applying a pattern to the sol-gel layer to form a patterned layer and applying a thermal decomposition treatment to the patterned layer to convert it to a hard mask layer.

(FIG. 2c)